

SPW



PATENT
Attorney Docket No. 04329.3304-00

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
Ayako NAKANO et al.) Group Art Unit: 1756
Application No.: 10/823,539) Examiner: Stephen D. ROSASCO
Filed: April 14, 2004)
For: PATTERN FORMING METHOD AND) Confirmation No.: 4440
SYSTEM, AND METHOD OF)
MANUFACTURING A)
SEMICONDUCTOR DEVICE)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

RESPONSE TO RESTRICTION REQUIREMENT

In a Restriction Requirement mailed March 1, 2007, the period for response to which extends through April 2, 2007 (April 1 is a Sunday), the Examiner required restriction under 35 U.S.C. § 121 between:

Group I: Claims 1-12 and 25¹, characterized by the Examiner as drawn to a mask pattern forming method and classified in class 430, subclass 5; and

Group II: Claims 13-24, characterized by the Examiner as drawn to a system for making a photomask and classified in class 716, subclass 21.

¹ The Restriction Requirement as mailed does not indicate whether pending claim 25 should be included in Group I or Group II, if either. In a telephone interview on March 30, 2007, Examiner Rosasco explained that claim 25 should have been included in Group I.

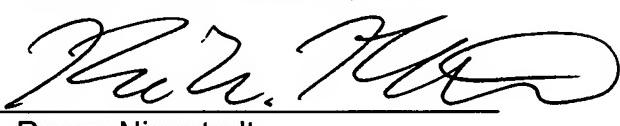
Applicants elect to prosecute Group I, claims 1-12 and 25, without traverse.

Please grant any extensions of time required to enter this response and charge
any additional required fees to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,
GARRETT & DUNNER, L.L.P.

Dated: April 2, 2007

By: 

Reece Nienstadt
Reg. No. 52,072

RVB/RWN